Application No.: 10/015,701 Docket No.: 8733.479.00-US

Amendment dated April 8, 2004

Reply to Office Action dated January 8, 2004

Listing of Claims:

1. (Original) A method of forming a liquid crystal display device comprising:

forming a thin film transistor and a pixel electrode on a first substrate;

forming a dielectric frame having a first height and a sealant having a second height on a second substrate, the first height of the dielectric frame being different from the second height of the sealant;

dispensing liquid crystal on the first substrate; and attaching the first and second substrates to each other.

- 2. (Original) The method of claim 1, wherein the sealant includes a material hardened by ultraviolet ray.
- 3. (Currently Amended) The method of claim 1, wherein the sealant includes a double sealant structure.
- 4. (Original) The method of claim 1, further comprising forming an electric field inducing window in the pixel electrode.
- 5. (Currently Amended) The method of claim 4, wherein the electric field inducing window has a slit shape or a hole substantially circular shape.
- 6. (Withdrawn) The method of claim 1, wherein forming the thin film transistor includes: forming a gate electrode on the first substrate; forming a gate insulating film on the first substrate;

forming a semiconductor layer on the gate insulating film; and

forming source and drain electrodes on the semiconductor layer.

- 7. (Currently Amended) The method of claim 1, wherein the thin film transistor is formed to have an L-shaped channel.
- 8. (Withdrawn) The method of claim 1, wherein the thin film transistor is formed to have a U-shape.

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9. (Original) The method of claim 1, wherein the dielectric frame drives the liquid crystal in various directions.

- 10. (Original) The method of claim 1, wherein the second height of the sealant is higher than the first height of the dielectric frame.
- 11. (Original) The method of claim 10, wherein a height difference between the sealant and the dielectric frame is more than $1\mu m$.
- 12. (Original) The method of claim 1, further comprising forming a common electrode on the second substrate.
- 13. (Original) The method of claim 12, wherein the dielectric frame is formed on the common electrode.
- (Original) The method of claim 1, further comprising forming an alignment layer on at least one of the first and second substrates.
- 15. (Original) The method of claim 14, wherein the alignment layer is selected from the group consisting of polyimide, polyamide, polyvinyl alcohol, polyamic acid, and silicon oxide.
- 16. (Withdrawn) The method of claim 14, wherein the alignment layer is selected from the group consisting of polyvinylcinnamate, polysiloxanecinnamate, and cellulosecinnamate.
- 17. (Original) The method of claim 1, further comprising forming a phase difference film on at least one of the first and second substrates.
- 18. (Original) The method of claim 17, wherein the phase difference film includes a negative uniaxial film.
- 19. (Currently Amended) The method of claim <u>17</u>[[1]], wherein the phase difference film includes a negative biaxial film.
- 20. (Original) The method of claim 1, wherein the first height is a range of 1-2 μ m and the second height is in a range of 5-8 μ m.

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21. (Withdrawn) The method of claim 1, wherein the first height is a range of 1-2 μ m and the second height is about 4 μ m.

- 22. (Withdrawn) The method of claim 1, wherein the first height is a range of 1-1.5 μ m and the second height is about 3 μ m.
- 23. (Withdrawn) The method of claim 1, wherein the first height is about 1 μ m and the second height is about 2 μ m.
- 24. (Withdrawn) A method of forming a liquid crystal display device comprising:

forming a gate electrode on a first substrate;

forming a gate insulating film on the gate electrode and the first substrate;

forming a semiconductor layer on the gate insulating film;

forming source and drain electrodes on the semiconductor layer;

forming a pixel electrode contacting the drain electrode, the pixel electrode including an electric field inducing window;

forming a dielectric frame having a first height and a sealant having a second height on a second substrate, the first height of the dielectric frame being different from the second height of the sealant, the dielectric frame capable of causing an electric field distortion;

dispensing liquid crystal on the first substrate; and attaching the first and second substrates to each other.

- 25. (Withdrawn) The method of claim 24, wherein the first height is a range of 1-2 μ m and the second height is in a range of 5-8 μ m.
- 26. (Withdrawn) The method of claim 24, wherein the first height is a range of 1-2 μ m and the second height is about 4 μ m.
- 27. (Withdrawn) The method of claim 24, wherein the first height is a range of 1-1.5 μ m and the second height is about 3 μ m.
- 28. (Withdrawn) The method of claim 24, wherein the first height is about 1 μ m and the second height is about 2 μ m.